

	Hit s	Search Text	DBs
1	2	((wafer or substrate or device) same (photosensitive or photoresist or resist) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((light or radiation or illuminat\$4) same (mirror near16 array) same (pluralit\$4 or multiple) same piston same interference)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	6	((wafer or substrate or device) same (photosensitive or photoresist or resist) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((light or radiation or illuminat\$4) same (mirror near16 array) same (pluralit\$4 or multiple) displac\$6 same interference) and (piston same (pluralit\$5 or multiple) same (irradiat\$4 or illuminat\$4 or light))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
3	7	((wafer or substrate or device) same (photosensitive or photoresist or resist) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((light or radiation or illuminat\$4) same (mirror near16 array) same (pluralit\$4 or multiple) displac\$6 same interference) and (piston same (pluralit\$5 or multiple) same array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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4	16	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and ((mirror near16 array) same (pluralit\$4 or multiple) displac\$6 same interference) and (piston same (pluralit\$5 or multiple))	US-PPGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
5	6	(wafer or substrate or device) and (mirror same tilt\$4) and (piston same (pluralit\$5 or multiple) same (displac\$6 or interference)) and modulat\$4	US-PPGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	8	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and ((mirror near16 array) same tilt\$4) and (piston same (pluralit\$5 or multiple)) and modulat\$4	US-PPGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
7	26	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and ((mirror near16 array) same tilt\$4) and ((piston or adjust\$4) same (pluralit\$5 or multiple)) and (modulat\$4 or SLM) and interference	US-PPGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	5	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and ((mirror near16 array) same tilt\$4) and ((piston or adjust\$4) same (pluralit\$5 or multiple)) and (modulat\$4 or SLM) and interfer\$5 and (displac\$6 near22 mirror) and (phase\$4 near16 (difference or shift\$4))	US-PPGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
9	5	(wafer or substrate or device) and (photosensitive or photoresist or resist) and ((mirror near16 array) same tilt\$4) and ((piston or adjust\$3) same (pluralit\$5 or multiple)) and (modulat\$4 or SLM) and interfer\$5 and (displac\$6 near22 mirror) and (phase\$4 near16 (difference or shift\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	12	(wafer or substrate or device) and (photosensitive or photoresist or resist) and ((mirror near16 array) same (torsion\$4 or tilt\$4)) and ((piston or adjust\$3) same (mirror or DMD)) and (modulat\$4 or SLM) and interfer\$5 and (displac\$6 near22 mirror) and (phase\$4 near16 (difference or shift\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	14	(wafer or substrate or device) and (photosensitive or photoresist or resist) and ((mirror near16 array) same (torsion\$4 or tilt\$4)) and piston and (modulat\$4 or SLM) and interfer\$5 and (phase\$4 near16 (difference or shift\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	18	((mirror near16 array) same (torsion\$4 or tilt\$4)) and piston and (modulat\$4 or SLM) and interfer\$5 and (phase\$4 near16 (difference or shift\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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13	11	(modulat\$4 same mirror same (torsion\$4 or tilt\$4) same (light or radiation or laser)) and ((piston or adjust\$2r) same modulat\$4) and interfer\$5 and (phase\$4 near16 (difference or shift\$4)) and (mirror same (displace\$4 or position\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	8	(modulat\$4 same \$6mirror same (torsion\$4 or tilt\$4) same (light or radiation or laser)) and ((piston or adjust\$2r) same modulat\$4) and interfer\$5 and (phase\$4 near16 (difference or shift\$4)) and \$6mirror and (displace\$4 or \$4position\$6 or (path near12 length))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	15	(modulat\$4 same \$6mirror same (torsion\$4 or tilt\$4 or angle) same (light or radiation or laser)) and ((piston or adjust\$2r) same modulat\$4) and interfer\$5 and (phase\$4 near16 (difference or shift\$4)) and \$6mirror and (displace\$4 or \$4position\$6 or (path near12 length))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
16	13	(\$8mirror same (torsion\$4 or tilt\$4 or angle) same (light or radiation or laser)) and ((piston or adjust\$2r) same (optical or mirror)) and interfer\$5 and diffract\$6 and ((phase\$4 near16 (difference or shift\$4 or profile or modulat\$4) same degree) and \$8mirror and (displac\$6 or \$4position\$6 or (path near12 length))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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17	0	(\$8mirror same (torsion\$4 or tilt\$4 or angle)) and ((piston or adjust\$2r) same (optical or mirror or modulat\$4 or (optical near9 element) or DOE)) and interfer\$5 and diffract\$6 and ((phase\$4 near16 (difference or shift\$4 or profile or modulat\$4)) same degree) and \$8mirror and (displac\$6 or \$4position\$6 or (path near12 length)) and (modualt\$5 same (light or laser or radiation))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	21	(\$8mirror same (torsion\$4 or tilt\$4 or angle)) and ((piston or adjust\$2r) same (optical or mirror or modulat\$4 or (optical near9 element) or DOE)) and interfer\$5 and diffract\$6 and ((phase\$4 near16 (difference or shift\$4 or profile or modulat\$4)) same degree) and \$8mirror and (displac\$6 or \$4position\$6 or (path near12 length)) and (modulat\$5 same (light or laser or radiation))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
19	10	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and (mirror same tilt\$4) and ((piston or adjust\$4) same (pluralit\$5 or multiple) same resolution) and (modulat\$4 or SLM) and interference	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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20	0	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and (mirror same tilt\$4) and (piston same (pluralit\$5 or multiple) same resolution)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	9	(mirror same tilt\$4) and (piston same (pluralit\$5 or multiple) same resolution)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
22	56	((\\$8mirror or DMD or MEMS or SLM) same (torsion\$4 or tilt\$4) same (phase\$4 near16 (difference or shift\$4)) same degree)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	10	((\\$8mirror or DMD or MEMS or SLM) same (torsion\$4 or tilt\$4) same (phase\$4 near16 (difference or shift\$4)) same degree) and ((wafer or substrate or target) same (photosensitive or photoresist or resist) same (expos\$4 or illuminat\$4 or irradiat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	18	(piston same (optical or mirror or modulat\$4 or (optical near9 element) or DOE) same (phase\$4 near16 (difference or shift\$4)) same degree) and (displac\$6 or \$4position\$6 or (path near12 length))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	22	(piston same (phase\$4 near16 (difference or shift\$4)) same degree) and ((wafer or substrate) same (photosensitive or resist or photoresist))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB